

Supporting information

Fabrication of cobalt gallium oxide with zinc iron oxide on nickel foam for high performance asymmetric supercapacitor

Akbar Mohammadi Zardkhoshoui^a, Saied Saeed Hosseiny Davarani^{a*}, Masumeh Hashemi^b

^a Faculty of Chemistry, Shahid Beheshti University, G. C., 1983963113, Evin, Tehran, Iran.

^b Chemistry & Materials Research Center, Niroo research institute, Tehran, Iran.

*Corresponding author, Tel: +98 21 22431661; Fax: +98 21 22431661.

E-mail addresses: ss-hosseiny@sbu.ac.ir (S.S.H. Davarani)

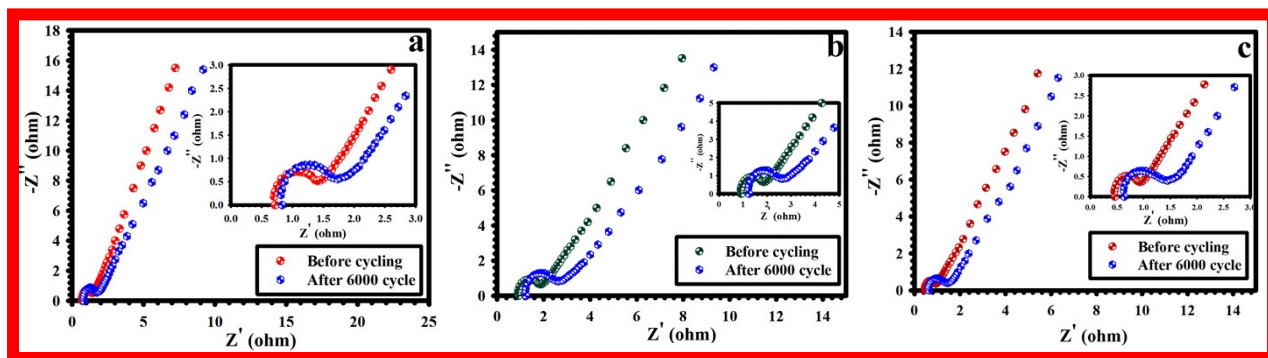


Fig. S1. (a) Nyquist plot of the CoGa_2O_4 (CGO)/nickel foam electrode in 2 M KOH solution before and after 6000 cycling. (b) Nyquist plot of the ZnFe_2O_4 (ZFO)/nickel foam electrode in 2 M KOH solution before and after 6000 cycling. (c) Nyquist plot of the our device before and after 6000 cycling

Table S1. Comparison of the electrochemical performance of CoGa_2O_4 (CGO)// ZnFe_2O_4 (ZFO) in three and two electrode systems with other previously reported electrodes.

Composition	Capacitance 3 and 2 electrodes (F g ⁻¹)	Cycles, retention 2 and 3 electrode	ED (W h kg ⁻¹) 2 Electrode	Synthesis method	Reference
NiCo ₂ O ₄ /GO	709.7 (3 E) 96.2 (2 E)	3000, 84.7 % (3 E) 5000, 94.3 (2 E)	34.4	Hydrothermal	1
rHGO/NiCo ₂ O ₄ @CF	1178 (3 E) 192.5 (2 E)	5000, 87.4 % (3 E) 5000, 82.7% (2 E)	74.88	Hydrothermal	2
NiCo ₂ O ₄	1229 (3 E) 68.7 (2 E)	3000, 86.3% (3 E) 2000, 87.8% (2 E)	21.5	Hydrothermal	3
CuCo ₂ O ₄	1330 (3 E)	5000, 93.6% (3 E)	29.55	Electrodeposition	4
Nickel-cobalt sulfide	1036 440 (3 E) 119.1 (2 E)	2000, 87% (3 E) 10000, 87.6% (2 E)	42.3	Hydrothermal	5
PCs/NiCo ₂ S ₄	605.2 (3 E) 190 (2 E)	5000, 91.3% (3 E) 5000, 92.7% (2 E)	23.3	Hydrothermal	6
CoGa ₂ O ₄ (Positive electrode) ZnFe ₂ O ₄ (Negative electrode)	1379.16 (3 E CoGa ₂ O ₄) 300.5 (3 E ZnFe ₂ O ₄) 232.2 (2 E) 352.30 (2 E)	6000, 96.6 (3 E CoGa ₂ O ₄) 6000, 91.1(3E ZnFe ₂ O ₄) 6000, 96.4 (2 E)	82.56	Electrodeposition	This work

References:

- 1 J. W. Mao, C. H. He, J. Q. Qi A. B. Zhang, Y. W. Sui, Y. Z. He, Q. K. Meng and F. X. Wei, *J. Electron. Mater.* 2018, **47**, 512-520.
- 2 S. Lia, K. Yang, P. Ye, H. Jiang, Z. Zhang, Q. Huang, L. Wang, *Appl. Surf. Sci.* 2019, **473**, 326-333.
- 3 K. Xu, J. Yang, J. Hu, *J. Colloid Interface Sci.* 2018, **511**, 456-462.
- 4 L. Abbasi, M. Arvand, *Appl. Surf. Sci.* 2018, **445**, 272-280.
- 5 L. F. Shen, L. Yu, H. B. Wu, X. Y. Yu, X. G. Zhang, X. W. Lou, *Nat. Commun.* 2015, **6**, 7694.
6. M. Yu, Y. Han, Y. Li, J. Li, L. Wang, *Appl. Surf. Sci.* 2019, **463**, 1001-1010.